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(54) Title: IN-SITU CONTROL OF FILM PROPERTIES DURING ATOMIC LAYER DEPOSITION

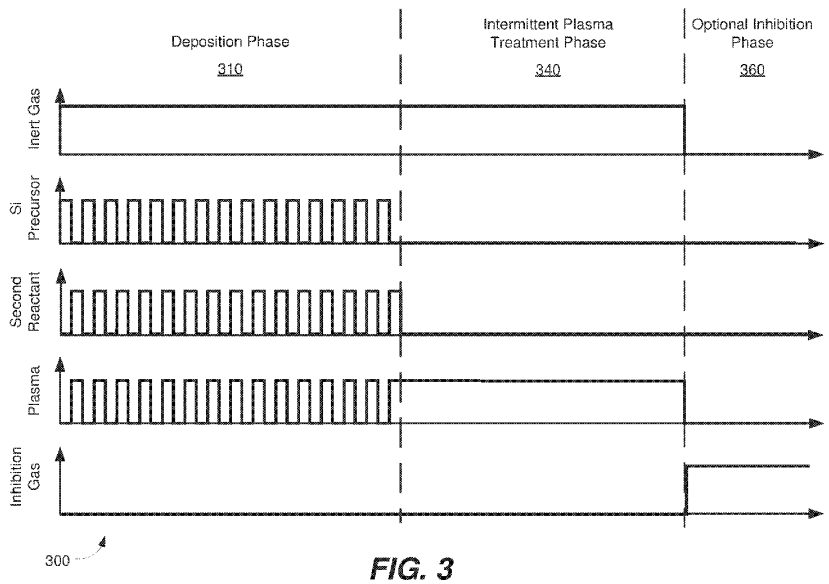


FIG. 3

(57) Abstract: Methods of providing control of film properties during atomic layer deposition using intermittent plasma treatment in-situ are provided herein. Methods include modulating gas flow rate ratios used to generate plasma during intermittent plasma treatment, toggling plasma power, and modulating chamber pressure.

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